



BENHA UNIVERSITY
FACULTY OF ENGINEERING (SHOUBRA)
ELECTRONICS AND COMMUNICATIONS ENGINEERING



CCE 201
Solid State Electronic Devices
(2022 - 2023) term 231

Lecture 5: PN junction.

Dr. Ahmed Samir

<https://bu.edu.eg/staff/ahmedsaied>

Outlines

**PN Junction with Open-Circuit
Terminals.**

The pn Junction with an Applied
Voltage.

Summary.

The PN Junction with Open-Circuit Terminals

➤ PN junction structure:

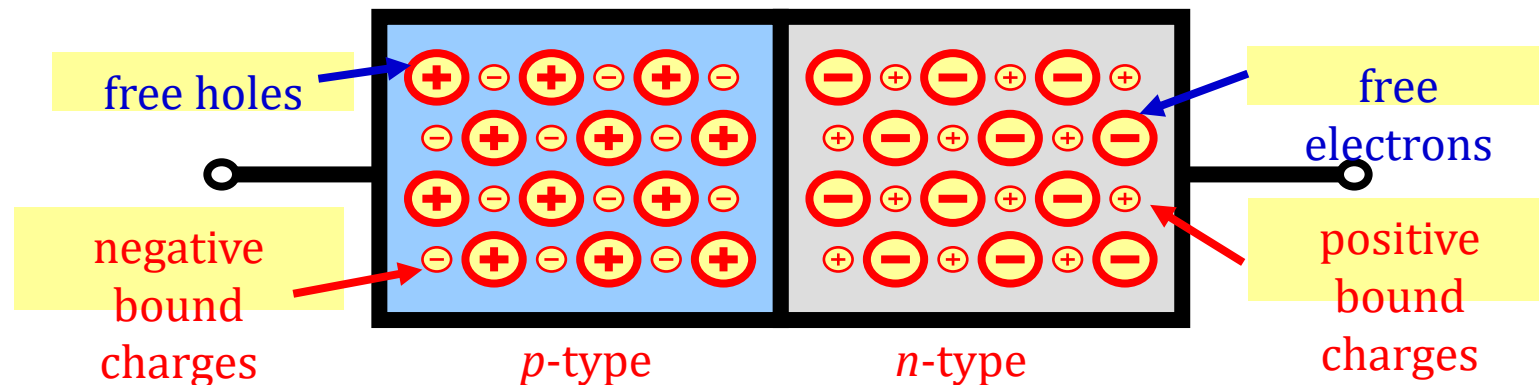
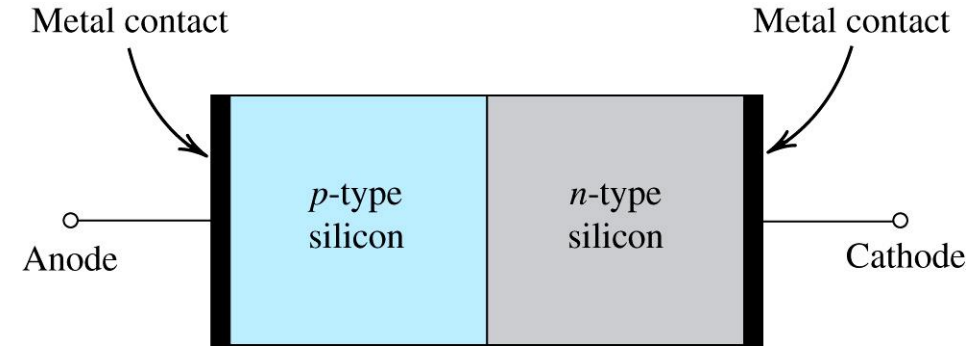
- ❑ p-type semiconductor
- ❑ n-type semiconductor
- ❑ metal contact for connection

➤ Q: What is state of pn junction with **open-circuit** terminals?

- ❑ **p-type** material contains **majority of holes**
These holes are **neutralized** by **equal amount of bound negative charge**.
- ❑ **n-type** material contains **majority of free electrons**
These electrons are **neutralized** by **equal amount of bound positive charge**.

➤ Bound charge

- ❑ Charge of opposite polarity to free electrons / holes of a given material.
- ❑ **Neutralizes the electrical charge** of these majority carriers.
- ❑ Does not affect **concentration gradients (current)**.

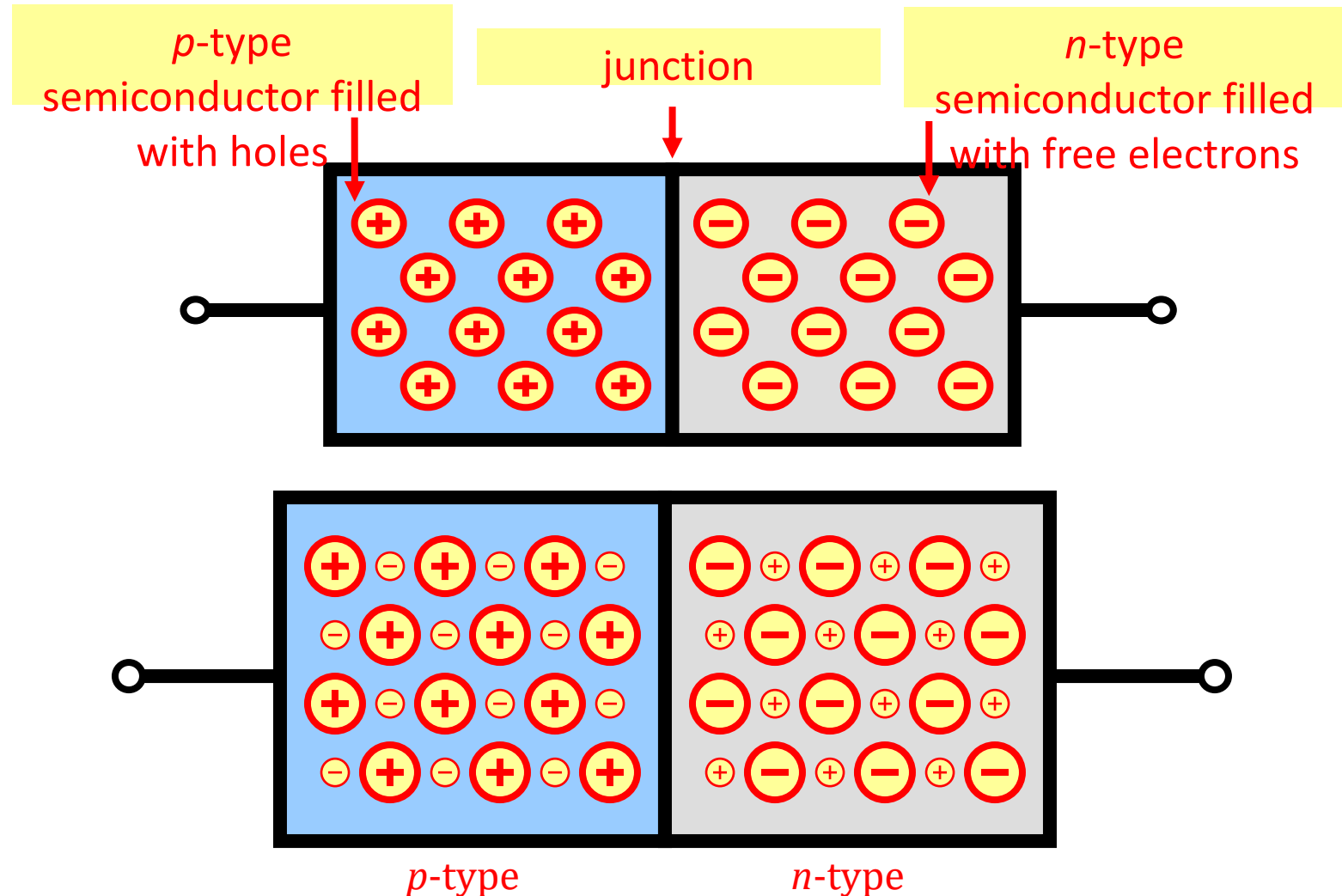


Operation with Open-Circuit Terminals

- What happens when a pn-junction is **newly formed**, when the p-type and n-type semiconductors **first touch one another**?

❑ **Step #1:** The p-type and n-type semiconductors **are joined at the junction**.

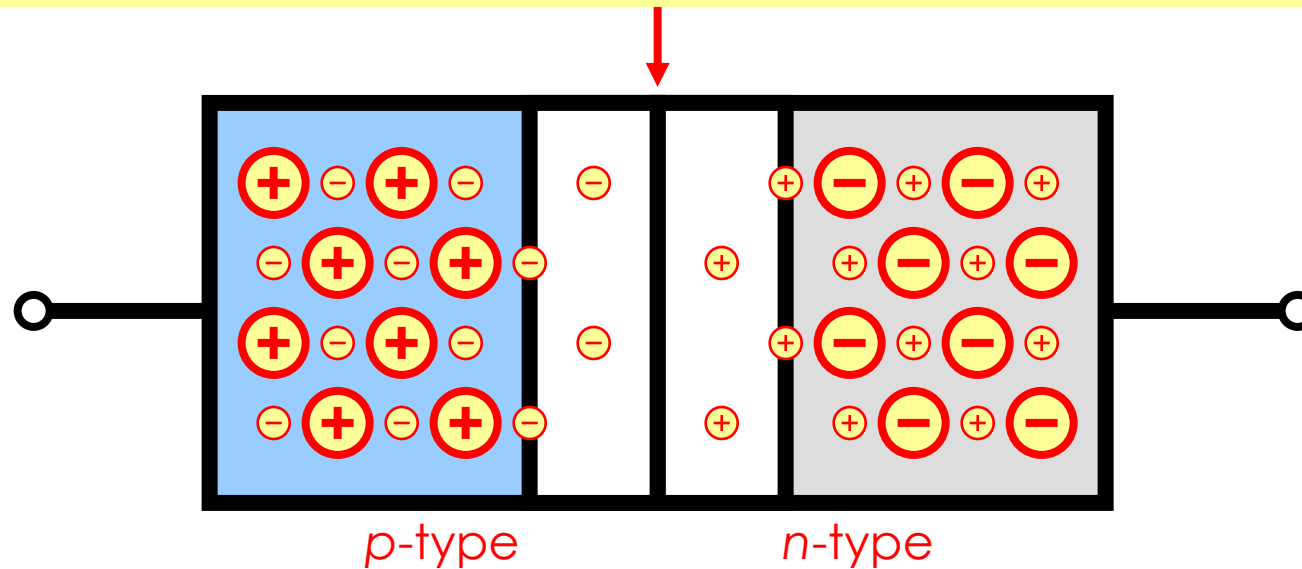
❑ **Step #2:** Diffusion begins. Those free electrons and holes which are closest to the junction will recombine and, essentially, eliminate one another.



Operation with Open-Circuit Terminals

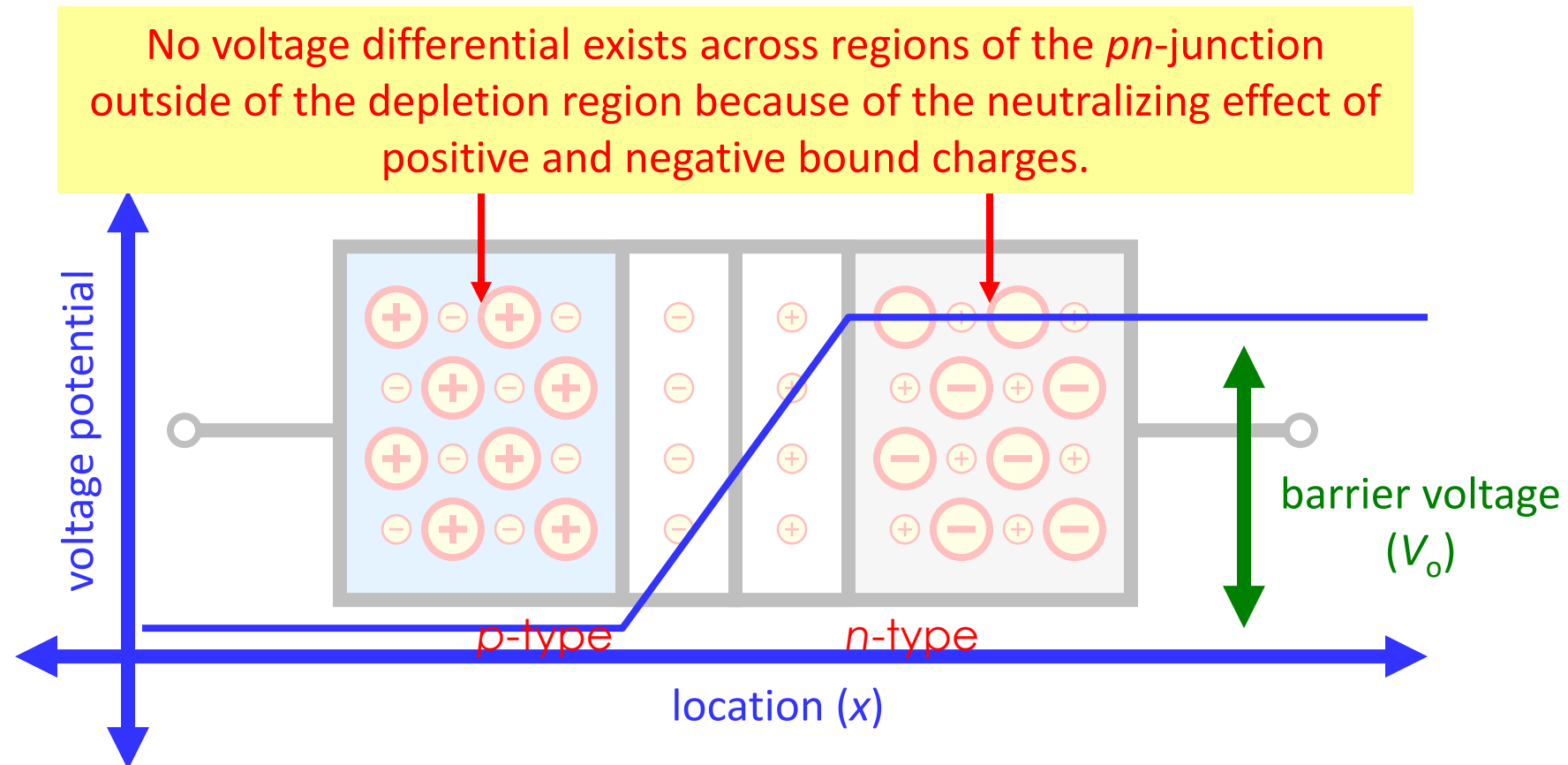
- **Step #3:** The **depletion region** begins to form – as diffusion occurs and free electrons recombine with holes.

The depletion region is filled with “uncovered” bound charges – who have lost the majority carriers to which they were linked.



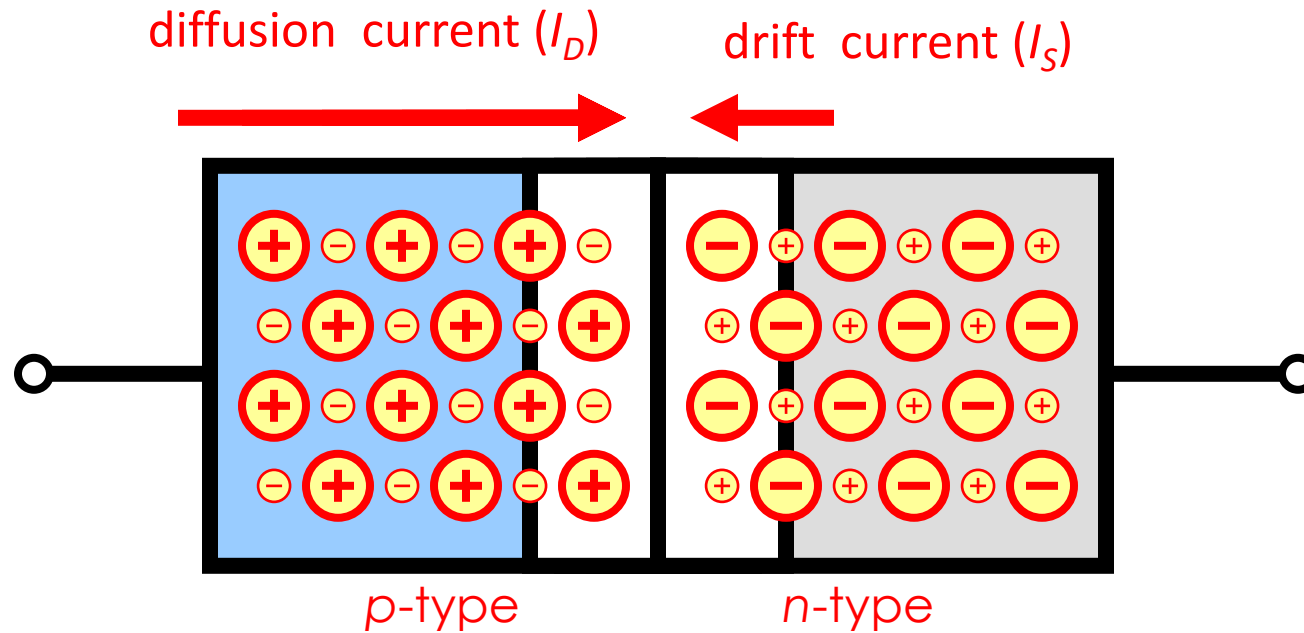
Operation with Open-Circuit Terminals

- **Step #4:** The “uncovered” bound charges affect a voltage differential across the depletion region. The magnitude of this barrier voltage (V_0) differential grows, as diffusion continues.



Operation with Open-Circuit Terminals

- Step #5: The barrier voltage (V_0) is an electric field whose polarity opposes the direction of diffusion current (I_D). As the magnitude of V_0 increases, the magnitude of I_D decreases.

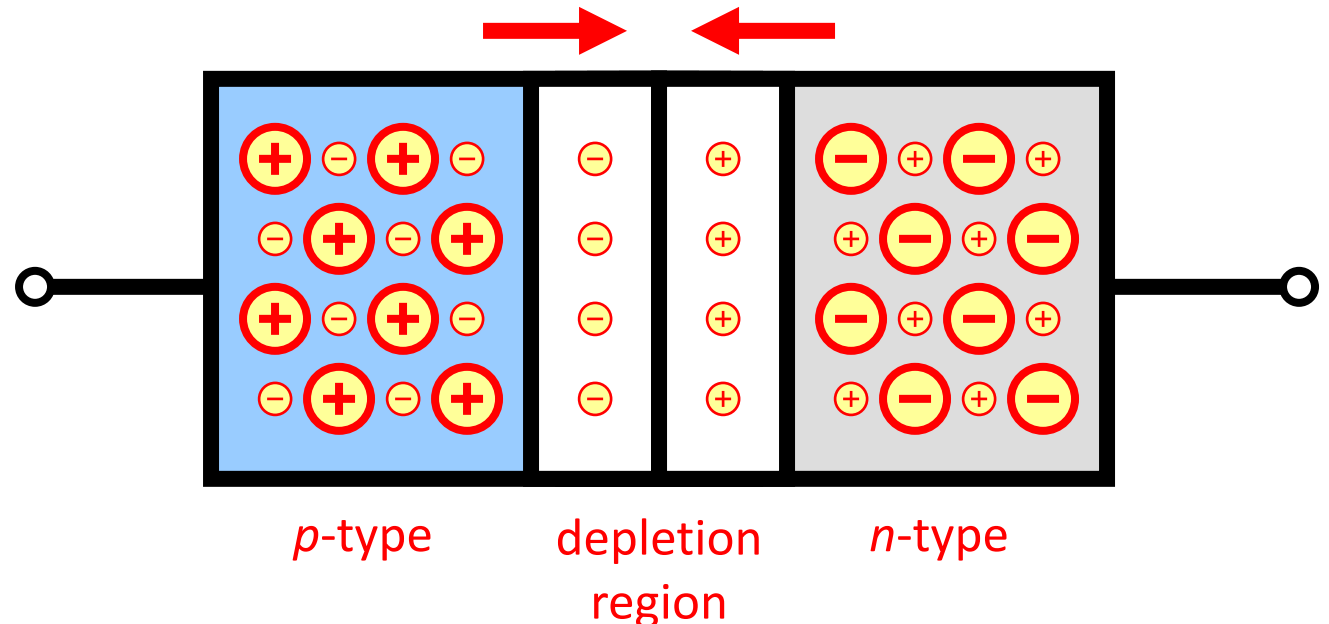


Operation with Open-Circuit Terminals

- **Step #6:** Equilibrium is reached, and diffusion ceases, once the magnitudes of diffusion and drift currents equal one another – resulting in **no net flow**.

- In addition to majority-carrier diffusion current (I_D), a component of current due to **minority carrier drift exists** (I_S).
- Specifically, some of the **thermally generated** in the p-type and n-type materials move toward and reach the edge of the depletion region.
- Therefore, they experience the electric field (V_0) in the depletion region and are swept across it.
- Unlike diffusion current, the polarity of V_0 reinforces this drift current.

Once equilibrium is achieved, no net current flow exists ($I_{net} = I_D - I_S$) within the *pn*-junction while under open-circuit condition.



Operation with Open-Circuit Terminals

- PN-junction built-in voltage (V_0) – is the equilibrium value of barrier voltage.
 - ❑ Generally, it takes on a value between **0.6 and 0.9V** for **silicon** at room temperature.
 - ❑ This voltage is applied across depletion region, not terminals of pn junction.
 - ❑ Power cannot be drawn from V_0 .

V_0 = barrier voltage

V_T = thermal voltage

N_A = acceptor doping concentration

N_D = donor doping concentration

n_i = concentration of free electrons...

...in intrinsic semiconductor

$$V_0 = V_T \ln \left(\frac{N_A N_D}{n_i^2} \right)$$

Report 1

- ❖ Prove that the pn - junction built -in voltage is given by:

$$V_0 = V_T \ln \left(\frac{N_A N_D}{n_i^2} \right)$$

- ❖ Hint: it can be derived from the equality of drift current and diffusion current at equilibrium.
- ❖ electron drift current = electron diffusion current.

Operation with Open-Circuit Terminals

- How is the **charge stored** in both sides of the depletion region defined?
- What information can be derived from this **equality**?

- In reality, the depletion region exists almost entirely on **one side** of the pn junction – due to great disparity between $N_A > N_D$.

$$qAx_p N_A = qAx_n N_D \rightarrow \frac{x_n}{x_p} = \frac{N_A}{N_D}$$

- Note that both x_p and x_n may be defined in terms of the depletion region width (W).

$$W = x_n + x_p = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) V_0}$$

$$x_n = W \frac{N_A}{N_A + N_D}$$

$$x_p = W \frac{N_D}{N_A + N_D}$$

$$Q_J = |Q_{\pm}| = Aq \left(\frac{N_A N_D}{N_A + N_D} \right) W$$

$$Q_J = A \sqrt{2\epsilon_s q \left(\frac{N_A N_D}{N_A + N_D} \right) V_0}$$

$|Q_+|$ = magnitude of charge on n -side of junction
 q = magnitude of electric charge
 A = cross-sectional area of junction
 x_n = penetration of depletion region into n -side
 N_D = concentration of donor atoms

$$|Q_+| = qAx_n N_D$$

$$|Q_-| = qAx_p N_A$$

$|Q_-|$ = magnitude of charge on p -side of junction
 q = magnitude of electric charge
 A = cross-sectional area of junction
 x_p = penetration of depletion region into p -side
 N_A = concentration of acceptor atoms

Summary :

- What has been learned about the pn-junction?
 - ❑ **Composition:** The pn junction is composed of **two silicon-based semiconductors**, one doped to be p-type and the other n-type.
 - ❑ **majority carriers:** Are generated by doping. Holes are present on p-side, free electrons are present on n-side.
 - ❑ **Bound charges:** charge of majority carriers are neutralized electrically by bound charges.
 - ❑ **Diffusion current I_D :** those majority carriers close to the junction will diffuse across, resulting in their elimination.
 - ❑ **Depletion region:** As these carriers disappear, they release bound charges and effect a voltage differential V_0 .
 - ❑ **Depletion-layer voltage:** As diffusion continues, the depletion layer voltage (V_0) grows, making diffusion more difficult and eventually bringing it to halt.
 - ❑ **Minority carriers:** Are generated thermally. Free electrons are present on p-side, holes are present on n-side.
 - ❑ **Drift current I_S :** The depletion-layer voltage (V_0) facilitates the **flow of minority** carriers to opposite side.
 - ❑ **Open circuit equilibrium $I_D = I_S$**

Outlines



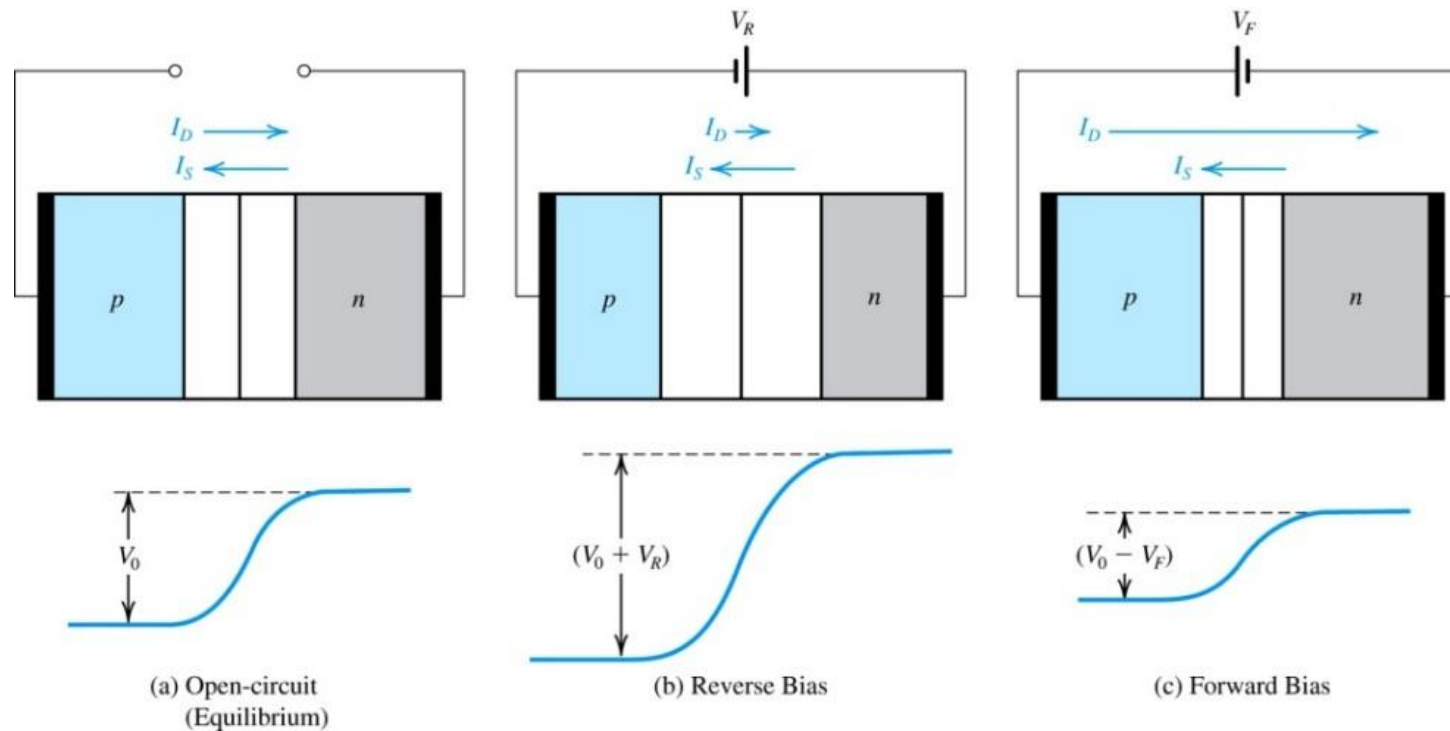
PN Junction with Open-Circuit
Terminals.

The pn Junction with an Applied
Voltage.

Summary.

The pn Junction with an Applied Voltage

- pn-junction under three conditions:
 - ▶ (a) **open-circuit** – where a barrier voltage V_0 exists.
 - ▶ (b) **reverse bias** – where a dc voltage V_R is applied.
 - ▶ (c) **forward bias** – where a dc voltage V_F is applied.



The pn Junction with an Applied Voltage

1) no voltage applied

2) voltage differential across depletion zone is V_0

3) $I_D = I_S$

1) negative voltage applied

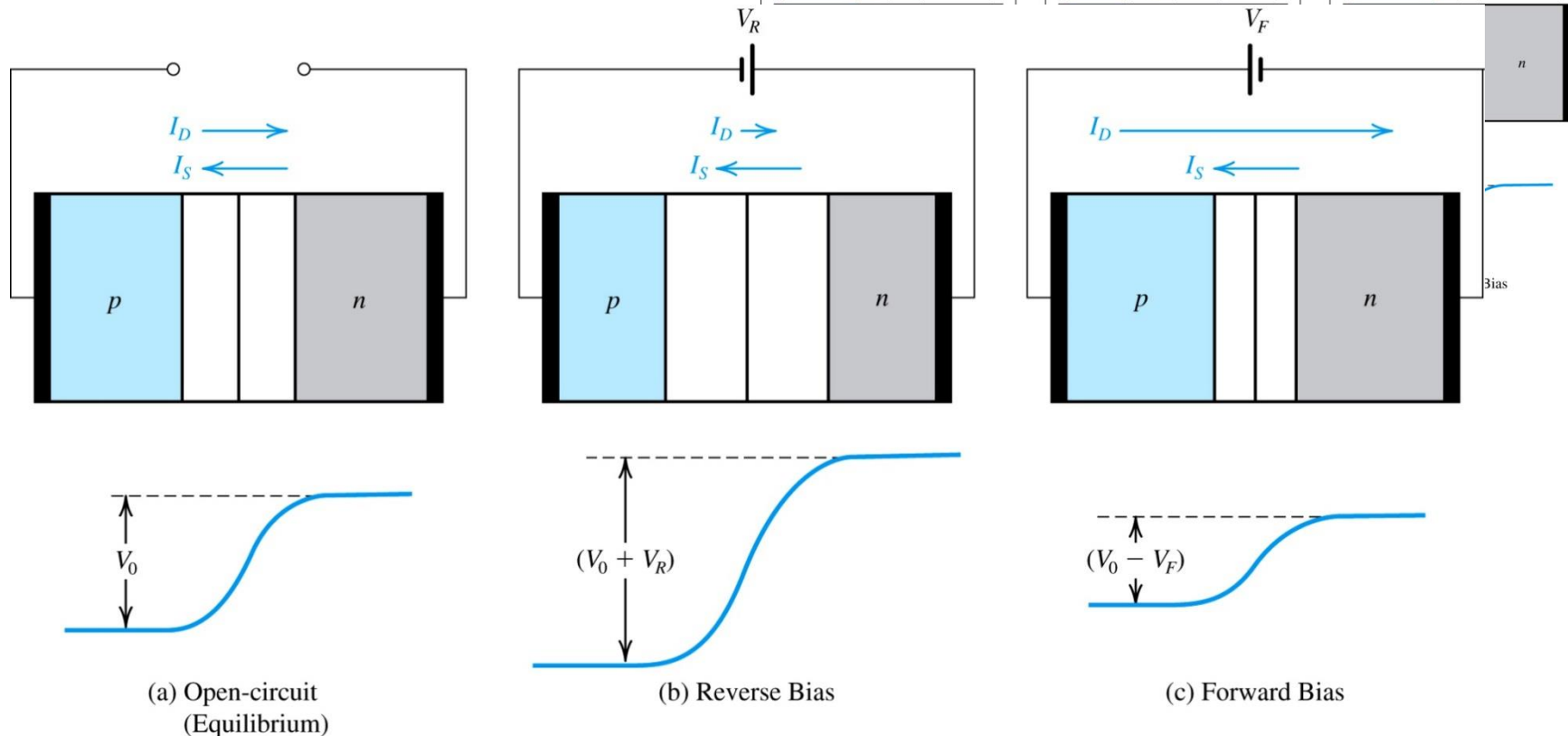
2) voltage differential across depletion zone is $V_0 + V_R$

3) $I_D < I_S$

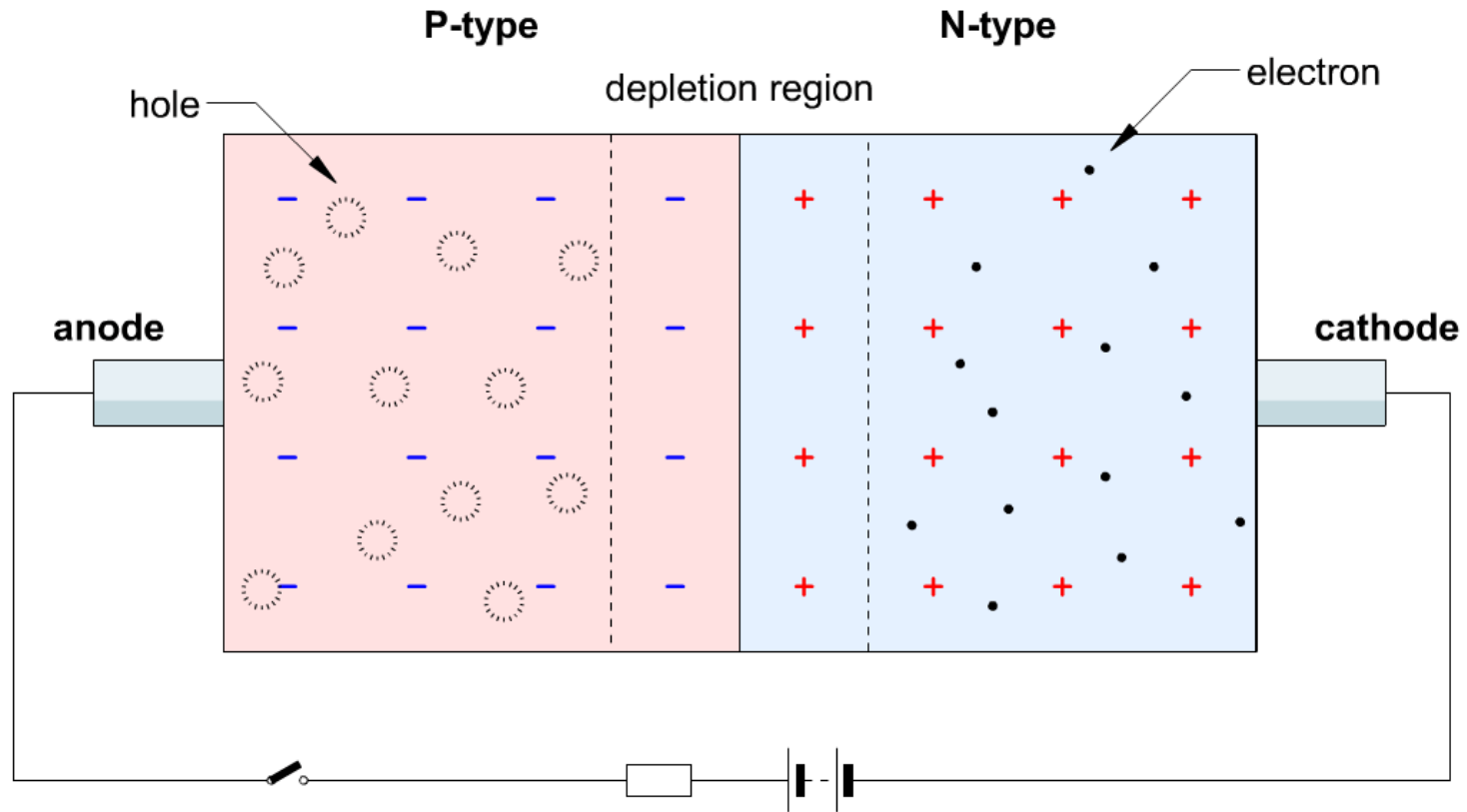
1) positive voltage applied

2) voltage differential across depletion zone is $V_0 - V_F$

3) $I_D > I_S$



The pn Junction with an Applied Voltage



The pn Junction with an Applied Voltage

reverse bias case

- the externally applied voltage V_R **adds to the barrier** voltage V_0
 - ...increase effective barrier
- this **reduces rate of diffusion**, reducing I_D
 - if $V_R > 1V$, I_D will fall to $0A$
- the drift current I_S **is unaffected**, but dependent on temperature
- result is that *pn* junction will **conduct small drift current I_S**

minimal current flows in reverse-bias case

forward bias case

- the externally applied voltage V_F **subtracts from the barrier** voltage V_0
 - ...decrease effective barrier
- this **increases rate of diffusion**, increasing I_D
- the drift current I_S **is unaffected**, but dependent on temperature
- result is that *pn* junction will **conduct significant current $I_D - I_S$**

significant current flows in forward-bias case

Forward-Bias Case

- Observe that **decreased** barrier voltage will be accompanied by...
 - (1) **decrease in stored uncovered charge** on both sides of junction
 - (2) **smaller depletion region**
- Width of depletion can given as:

ϵ_s = electrical permiability of silicon ($11.7\epsilon_0 = 1.04\text{E} - 12\text{F} / \text{cm}$)

$$W = x_n + x_p = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 - V_F)}$$

action:
replace V_0
with $V_0 - V_F$

$$Q_J = A \sqrt{2\epsilon_s q \left(\frac{N_A N_D}{N_A + N_D} \right) (V_0 - V_F)}$$

action:
replace V_0
with $V_0 - V_F$

$Q_J =$ magnitude of charge stored on either side of depletion region

Reverse-Bias Case

- Observe that **increased** barrier voltage will be accompanied by...
 - (1) **increase in stored uncovered charge on both sides of junction**
 - (2) **Wider depletion region**
- Width of depletion can given as:

ϵ_s = electrical permiability of silicon ($11.7\epsilon_0 = 1.04\text{E} - 12\text{F} / \text{cm}$)

$$W = x_n + x_p = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 + V_R)}$$

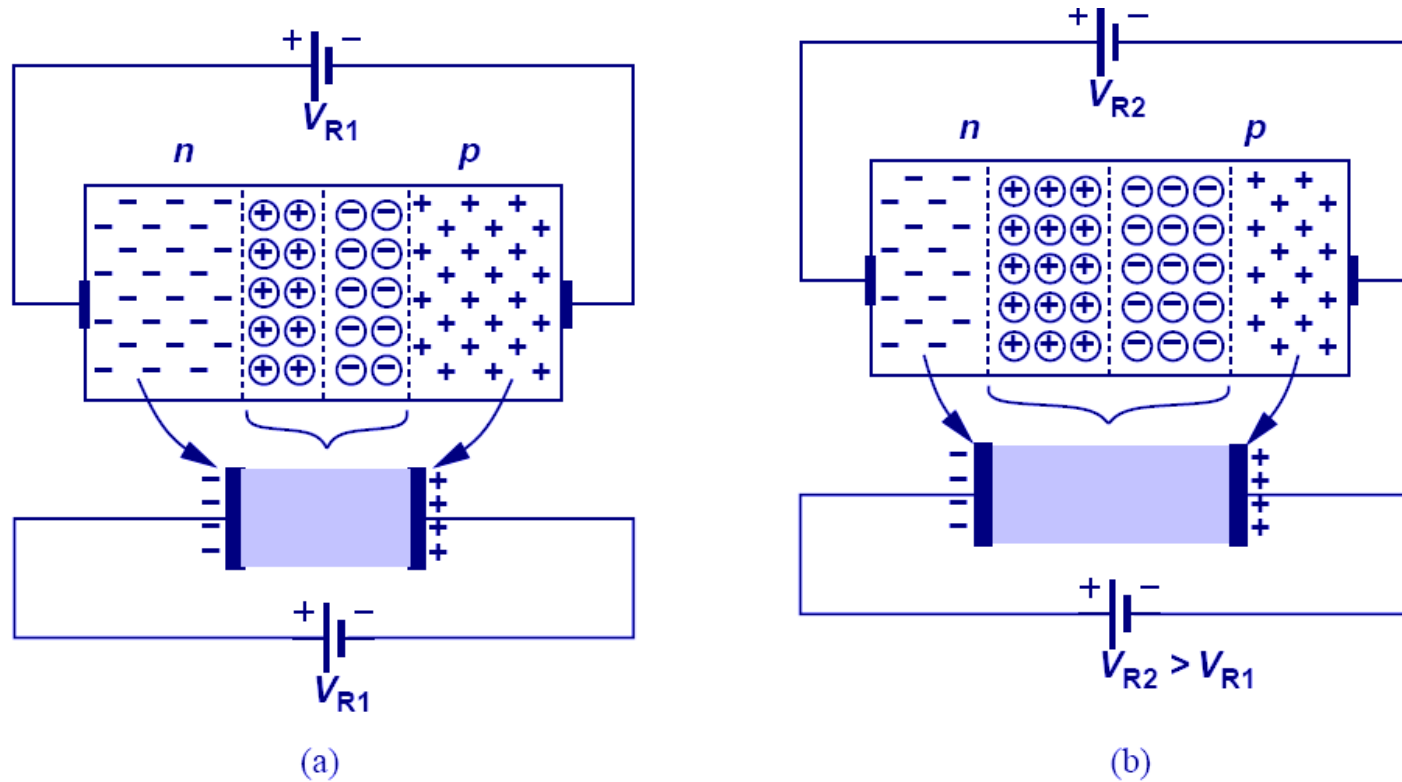
action:
replace V_0
with $V_0 + V_R$

$$Q_j = A \sqrt{2\epsilon_s q \left(\frac{N_A N_D}{N_A + N_D} \right) (V_0 + V_R)}$$

action:
replace V_0
with $V_0 + V_R$

$Q_j =$ magnitude of charge stored on either side of depletion region

Reverse Biased Diode's Application: Voltage-Dependent Capacitor



The PN junction can be viewed as a capacitor. By varying V_R , the depletion width changes, changing its capacitance value; therefore, the PN junction is actually a voltage-dependent capacitor.

Example 3.5

20

Consider a pn junction in equilibrium at room temperature ($T = 300$ K) for which the doping concentrations are $N_A = 10^{18}/\text{cm}^3$ and $N_D = 10^{16}/\text{cm}^3$ and the cross-sectional area $A = 10^{-4} \text{ cm}^2$. Calculate p_p , n_{p0} , n_n , p_{n0} , V_0 , W , x_n , x_p , and Q_J . Use $n_i = 1.5 \times 10^{10}/\text{cm}^3$.

Solution

$$\begin{aligned}p_p &\simeq N_A = 10^{18} \text{ cm}^{-3} \\n_{p0} &= \frac{n_i^2}{p_p} \simeq \frac{n_i^2}{N_A} = \frac{(1.5 \times 10^{10})^2}{10^{18}} = 2.25 \times 10^2 \text{ cm}^{-3} \\n_n &\simeq N_D = 10^{16} \text{ cm}^{-3} \\p_{n0} &= \frac{n_i^2}{n_n} \simeq \frac{n_i^2}{N_D} = \frac{(1.5 \times 10^{10})^2}{10^{16}} = 2.25 \times 10^4 \text{ cm}^{-3} \\V_0 &= V_T \ln\left(\frac{N_A N_D}{n_i^2}\right)\end{aligned}$$

where

$$\begin{aligned}V_T &= \frac{kT}{q} = \frac{8.62 \times 10^{-5} \times 300 \text{ (eV)}}{q \text{ (e)}} \\&= 25.9 \times 10^{-3} \text{ V}\end{aligned}$$

Thus,

$$\begin{aligned}V_0 &= 25.9 \times 10^{-3} \ln\left(\frac{10^{18} \times 10^{16}}{2.25 \times 10^{20}}\right) \\&= 0.814 \text{ V}\end{aligned}$$

To determine W we use Eq. (3.26):

$$\begin{aligned} W &= \sqrt{\frac{2 \times 1.04 \times 10^{-12}}{1.6 \times 10^{-19}} \left(\frac{1}{10^{18}} + \frac{1}{10^{16}} \right) \times 0.814} \\ &= 3.27 \times 10^{-5} \text{ cm} = 0.327 \text{ } \mu\text{m} \end{aligned}$$

To determine x_n and x_p we use Eq. (3.27) and (3.28), respectively:

$$\begin{aligned} x_n &= W \frac{N_A}{N_A + N_D} \\ &= 0.327 \frac{10^{18}}{10^{18} + 10^{16}} = 0.324 \text{ } \mu\text{m} \end{aligned}$$

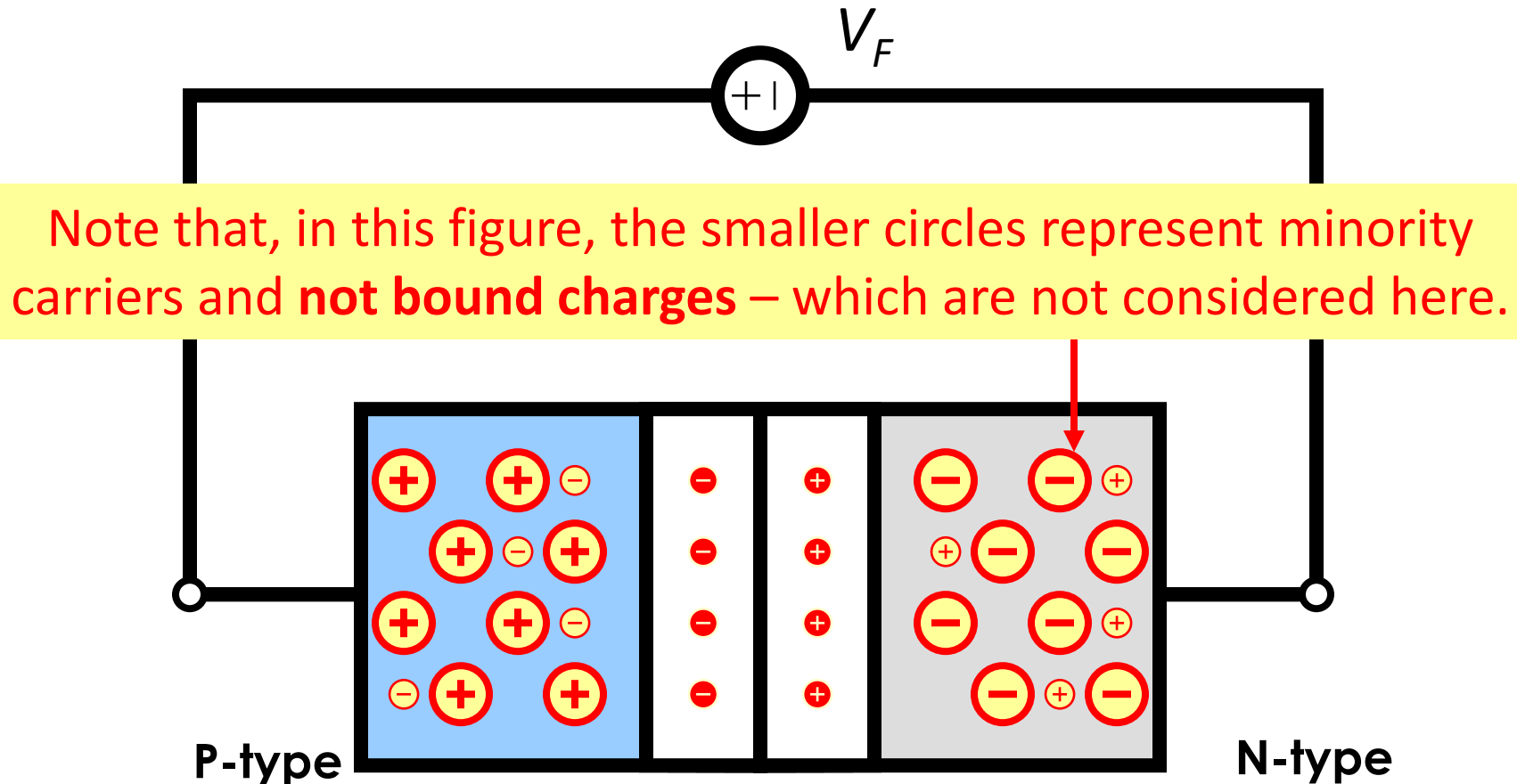
$$\begin{aligned} x_p &= W \frac{N_D}{N_A + N_D} \\ &= 0.327 \frac{10^{16}}{10^{18} + 10^{16}} = 0.003 \text{ } \mu\text{m} \end{aligned}$$

Finally, to determine the charge stored on either side of the depletion region, we use Eq. (3.29)

$$\begin{aligned} Q_j = |Q_{\pm}| &= Aq \left(\frac{N_A N_D}{N_A + N_D} \right) W \\ Q_j &= 10^{-4} \times 1.6 \times 10^{-19} \left(\frac{10^{18} \times 10^{16}}{10^{18} + 10^{16}} \right) \times 0.327 \times 10^{-4} \\ &= 5.18 \times 10^{-12} \text{ C} = 5.18 \text{ pC} \end{aligned}$$

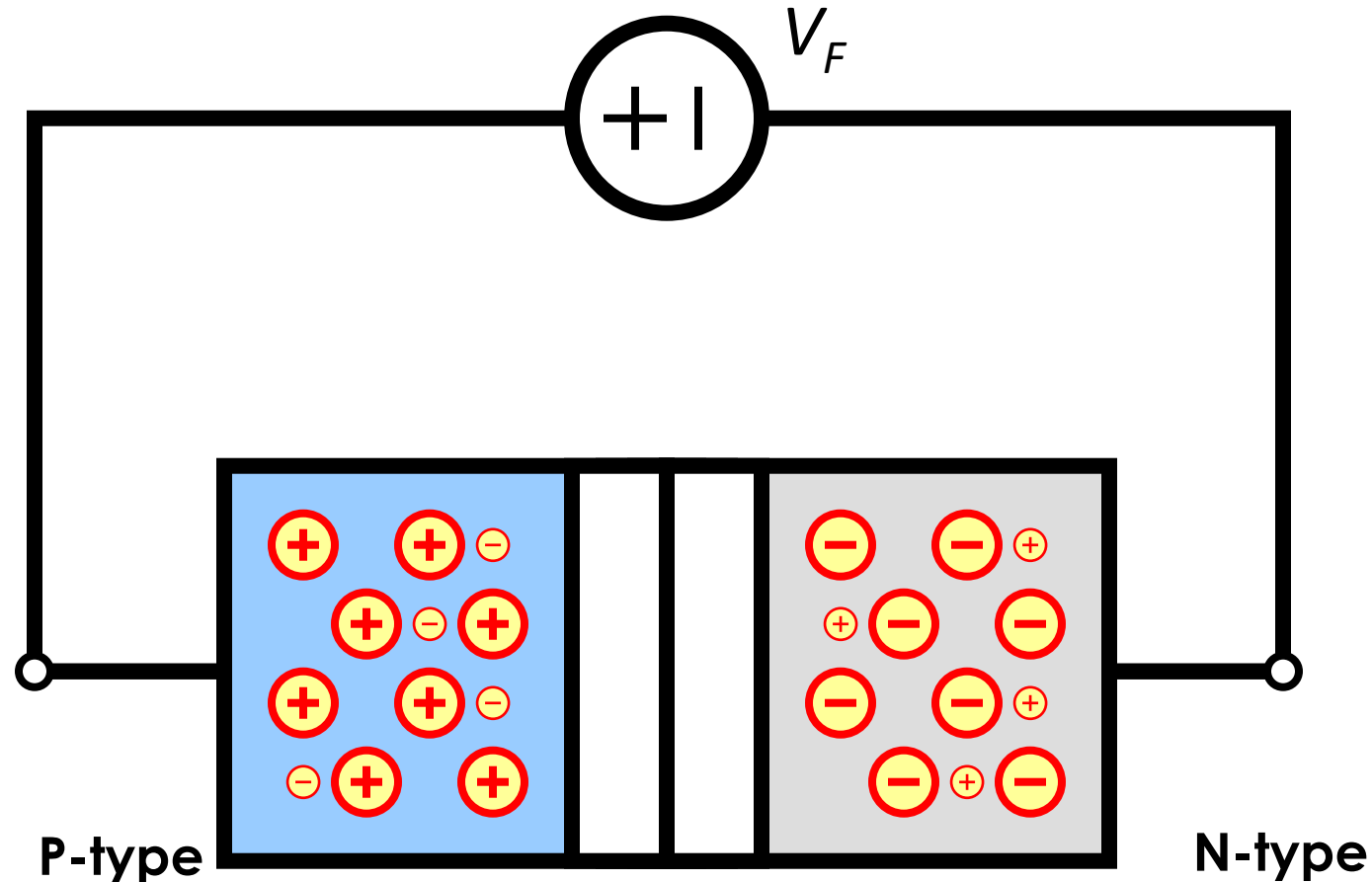
The Current-Voltage Relationship of the Junction

- What happens, exactly, when a forward-bias voltage (V_F) is applied to the pn-junction?
step #1: Initially, a small forward-bias voltage (V_F) is applied. It, because of its polarity, **pushes majority (holes in p -region and electrons in n -region) toward the junction** and reduces width of the depletion zone.



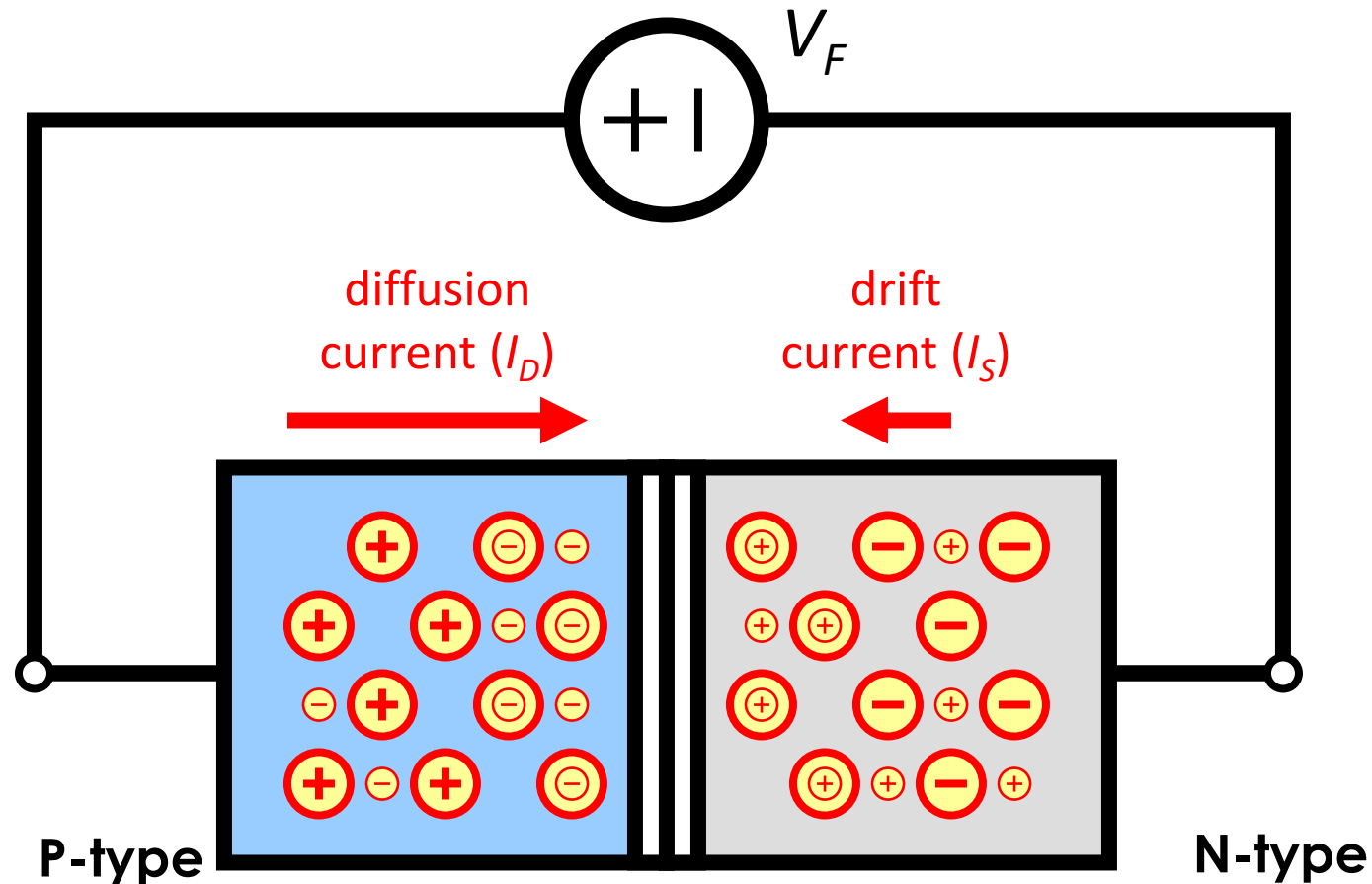
The Current-Voltage Relationship of the Junction

- **step #2:** As the magnitude of V_F increases, the **depletion zone becomes thin** enough such that the barrier voltage ($V_0 - V_F$) cannot stop diffusion current – as described in previous slides.



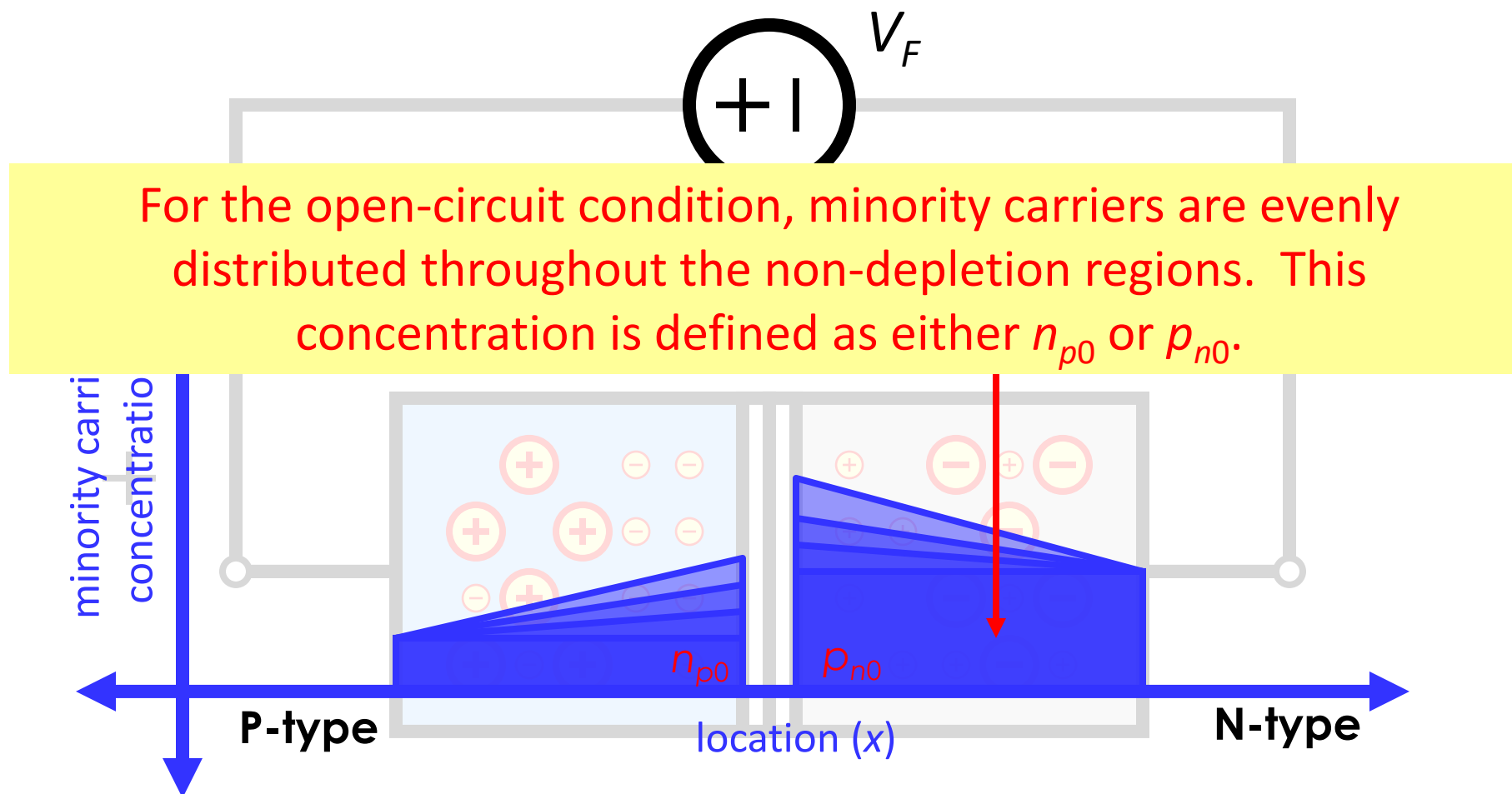
The Current-Voltage Relationship of the Junction

- **step #3:** Majority carriers (free electrons in n -region and holes in p -region) **cross the junction and become minority charge carriers** in the near-neutral region.



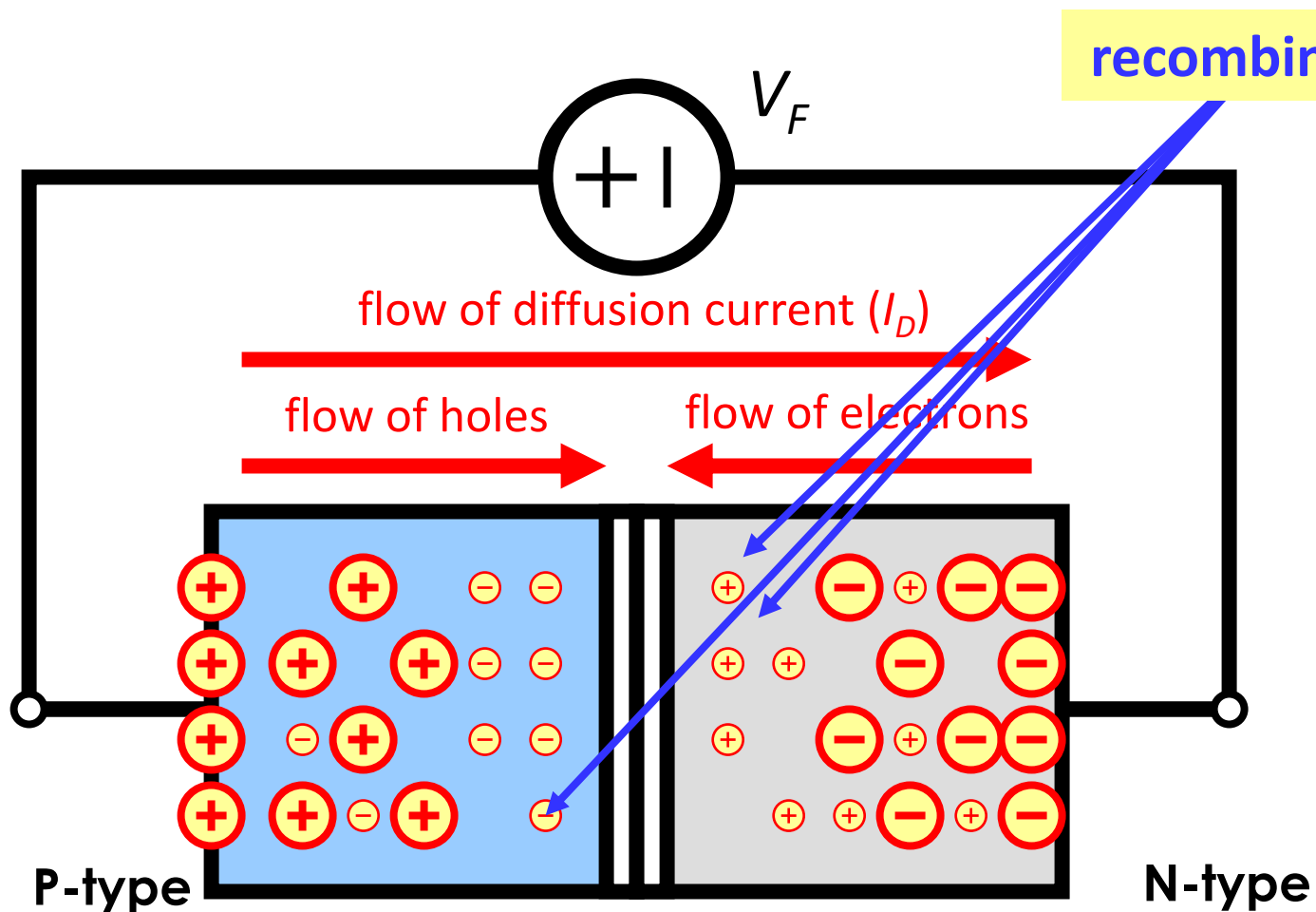
The Current-Voltage Relationship of the Junction

- **step #4:** The **concentration of minority charge carriers increases** on either side of the junction. A **steady-state gradient** is reached as rate of majority carriers crossing the junction equals that of recombination.

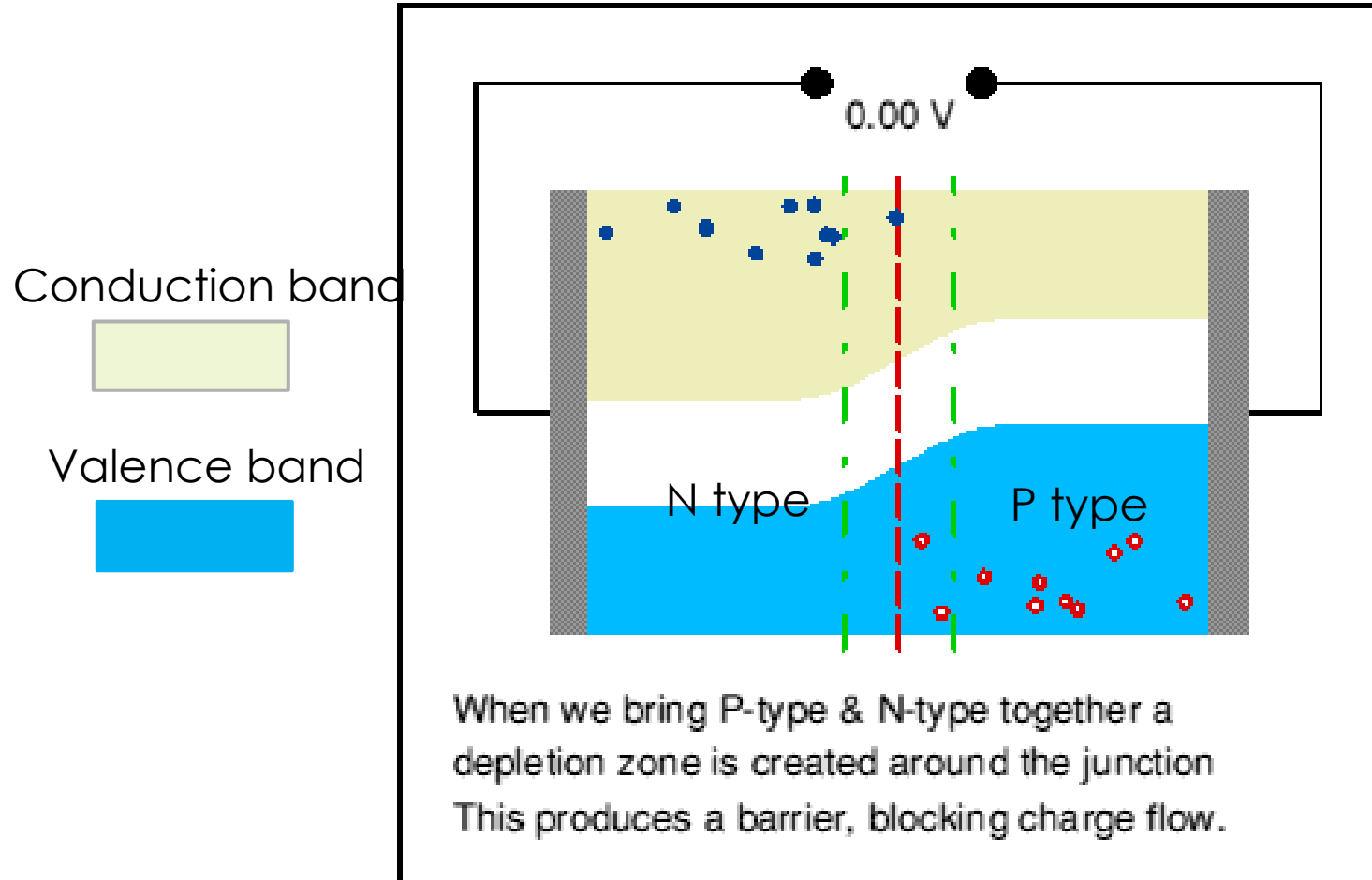


The Current-Voltage Relationship of the Junction

- **step #5:** Diffusion current is maintained – in spite low diffusion lengths (e.g. microns) and recombination – by constant flow of both free electrons and holes towards the junction.



The Current-Voltage Relationship of the Junction



The Current-Voltage Relationship of the Junction

For forward-biased case, how is **diffusion current (I_D)** defined?

$$I = \underbrace{\left(Aqn_i^2 \left[\frac{D_p}{L_p N_D} + \frac{D_n}{L_n N_A} \right] \right)}_{I_S} (e^{V/V_T} - 1) = I_S (e^{V/V_T} - 1)$$

- ▶ **saturation current (I_S)** – is the **maximum reverse current** which will flow through *pn*-junction.
 - ▶ It is proportional to **cross-section of junction** (A).
 - ▶ Typical value is $10^{-18}A$.

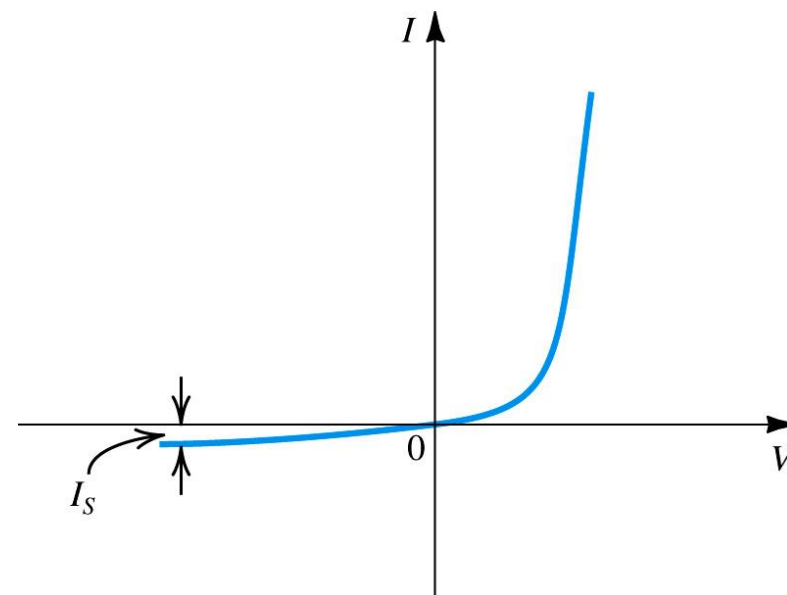


Figure 13: The *pn* junction I – V characteristic.

Example 6: pn -Junction

- ▶ Consider a forward-biased pn junction conducting a current of $I = 0.1 \text{ mA}$ with following parameters:
 - ▶ $N_A = 10^{18} / \text{cm}^3$, $N_D = 10^{16} / \text{cm}^3$, $A = 10^{-4} \text{ cm}^2$, $n_i = 1.5 \times 10^{10} / \text{cm}^3$, $L_p = 5 \text{ } \mu\text{m}$, $L_n = 10 \text{ } \mu\text{m}$, D_p (n -region) = $10 \text{ cm}^2 / \text{s}$, D_n (p -region) = $18 \text{ cm}^2 / \text{s}$
- ▶ **Q(a):** Calculate I_S .
- ▶ **Q(b):** Calculate the forward bias voltage (V).
- ▶ **Q(c):** Component of current I due to hole injection and electron injection across the junction.

(a)
$$I_S = Aqn_i^2 \left(\frac{D_p}{L_p N_D} + \frac{D_n}{L_n N_A} \right)$$

$$I_S = 10^{-4} \times 1.6 \times 10^{-19} \times (1.5 \times 10^{10})^2 \times \left(\frac{10}{5 \times 10^{-4} \times 10^{16}} + \frac{18}{10 \times 10^{-4} \times 10^{18}} \right)$$

$$= 7.3 \times 10^{-15} \text{ A}$$

(b) In the forward direction,

$$I = I_S (e^{V/V_T} - 1)$$

$$\simeq I_S e^{V/V_T}$$

Thus,

$$V = V_T \ln \left(\frac{I}{I_S} \right)$$

For $I = 0.1 \text{ mA}$,

$$V = 25.9 \times 10^{-3} \ln \left(\frac{0.1 \times 10^{-3}}{7.3 \times 10^{-15}} \right)$$

$$= 0.605 \text{ V}$$

(c) The hole-injection component of I can be found using Eq. (3.37)

$$\begin{aligned} I_p &= Aq \frac{D_p}{L_p} p_{n0} (e^{V/V_T} - 1) \\ &= Aq \frac{D_p}{L_p} \frac{n_i^2}{N_D} (e^{V/V_T} - 1) \end{aligned}$$

Similarly I_n can be found using Eq. (3.39),

$$I_n = Aq \frac{D_n}{L_n} \frac{n_i^2}{N_A} (e^{V/V_T} - 1)$$

Thus,

$$\frac{I_p}{I_n} = \left(\frac{D_p}{D_n} \right) \left(\frac{L_n}{L_p} \right) \left(\frac{N_A}{N_D} \right)$$

For our case,

$$\frac{I_p}{I_n} = \frac{10}{18} \times \frac{10}{5} \times \frac{10^{18}}{10^{16}} = 1.11 \times 10^2 = 111$$

Thus most of the current is conducted by holes injected into the n region.

Specifically,

$$I_p = \frac{111}{112} \times 0.1 = 0.0991 \text{ mA}$$

$$I_n = \frac{1}{112} \times 0.1 = 0.0009 \text{ mA}$$

This stands to reason, since the p material has a doping concentration 100 times that of the n material.



END OF LECTURE

BEST WISHES